

Welcome to IEEE Xplore®

- Home
- What Can I Access?
- Log-out

Tables of Contents

- Journals & Magazines
- Conference Proceedings
- Standards

Search

- By Author
- Basic
- Advanced

Member Services

- Join IEEE
- Establish IEEE Web Account

 Print Format

Your search matched 15 of 787871 documents.

Results are shown 15 to a page, sorted by publication year in descending order.

You may refine your search by editing the current search expression or entering a new one in the text box.

Then click **Search Again**.

native <and> mos

Results:

Journal or Magazine = **JNL** Conference = **CNF** Standard = **STD**

1 Highly hydrogen-sensitive Pd/InP metal-oxide-semiconductor Schottky diode hydrogen sensor

Pan, H.J.; Lin, K.W.; Yu, K.H.; Cheng, C.C.; Thei, K.B.; Liu, W.C.; Chen, H.I.

Electronics Letters, Volume: 38 Issue: 2, 17 Jan. 2002

Page(s): 92 -94

[\[Abstract\]](#) [\[PDF Full-Text \(318 KB\)\]](#) **JNL**

2 Monolithic InGaAsP optoelectronic devices with silicon electronics

Fehly, D.; Schlachetzki, A.; Bakin, A.S.; Gutzzeit, A.; Wehmann, H.-H.

Quantum Electronics, IEEE Journal of, Volume: 37 Issue: 10, Oct. 2001

Page(s): 1246 -1252

[\[Abstract\]](#) [\[PDF Full-Text \(168 KB\)\]](#) **JNL**

3 Numerical simulation of field effect transistors in 4H and 6H-SiC

Nilsson, H.E.; Bertilsson, K.; Dubanic, E.; Hjelm, M.

Wide Bandgap Layers, 2001. Abstract Book. 3rd International Conference on Novel Applications of, 2001

Page(s): 199 -200

[\[Abstract\]](#) [\[PDF Full-Text \(81 KB\)\]](#) **CNF**

4 High quality ultra-thin (2.4 nm) oxide prepared by clustered vertical furnace with in-situ HF-vapor pre-gate oxide cleaning

Chao, T.S.; Chen, J.L.; Lai, C.S.; Lin, H.C.; Huang, T.Y.

VLSI Technology, Systems, and Applications, 1999. International Symposium on, 199

Page(s): 74 -77

L Number	Hits	Search Text	DB	Time stamp
1	46	native near2 mos	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/08/07 08:56
2	98	((native or natural or intrinsic) same mos) and (transconductance or gyrator or (active near inductor))	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/08/07 08:57